

<b>Title</b>	<b>Develop and fit pattern for a garment of complex design</b>		
<b>Level</b>	<b>4</b>	<b>Credits</b>	<b>6</b>

<b>Purpose</b>	People credited with this unit standard are able to: develop a complex design concept; develop pattern pieces for complex design; cut, assemble, and fit toile for complex design; and produce pattern pieces for individual fit.
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<b>Classification</b>	Home and Life Sciences > Home and Life Sciences - Textile Technology
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<b>Available grade</b>	Achieved
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### Explanatory notes

#### Definitions

A garment of *complex design* describes a garment which includes more than one design feature in both upper and lower body parts of a garment, and the design will include at least four design features which are part of the structure of the garment. Examples of complex design could be but are not limited to – a ball gown, wedding outfit, stage costume, tailored jacket, overcoat.

*Design features* may include but are not limited to – silhouette such as shoulder shape; skirt or pants shape such as tight-fitting, baggy; frills; design lines such as princess, empire, yokes; neckline, collar; sleeves; openings, closures, fastenings.

*Toile* is the technical term for the trial garment made up in muslin or other cheap fabric so that fitting alterations and adjustments can be made.

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### Outcomes and evidence requirements

#### Outcome 1

Develop a complex design concept.

#### Evidence requirements

- 1.1 The development of the design concept is evident in working drawings.
- 1.2 The design concept illustration allows the design features to be identified.  
Range front view, back view.
- 1.3 The design concept illustration allows pattern pieces to be developed.

1.4 The design concept identifies the fabric, and other materials meet the requirements of the design concept.

Range fabric includes – lining if required, interfacing, fastenings.

**Outcome 2**

Develop pattern pieces for complex design.

**Evidence requirements**

2.1 Pattern pieces are developed to the requirements of the design concept.

**Outcome 3**

Cut, assemble, and fit toile for complex design.

**Evidence requirements**

3.1 The toile fabric is prepared to enable cutting and fitting to be completed.

Range pressing, grain markings, secure pattern pieces.

3.2 The toile is cut to pattern shapes, pattern markings are transferred, and the toile is assembled to enable fitting.

3.3 The toile is fitted to identify alterations and adjustments.

3.4 Alterations are carried out, and the toile is refitted to ensure fit is appropriate for the wearer and consistent with the design concept.

**Outcome 4**

Produce pattern pieces for individual fit.

**Evidence requirements**

4.1 Design and fitting lines on toile are marked to enable transfer to pattern pieces.

4.2 The pattern pieces prepared include all markings, symbols, and information for cutting and construction.

4.3 Construction details are documented to enable fabric and notions to be purchased, and the garment to be assembled.

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<b>Planned review date</b>	31 December 2014
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**Status information and last date for assessment for superseded versions**

Process	Version	Date	Last Date for Assessment
Registration	1	26 March 1996	31 December 2013
Revision	2	6 October 1999	31 December 2013
Review	3	28 November 2002	31 December 2013
Review	4	16 August 2012	N/A

**Consent and Moderation Requirements (CMR) reference**

0134

This CMR can be accessed at <http://www.nzqa.govt.nz/framework/search/index.do>.

**Please note**

Providers must be granted consent to assess against standards (accredited) by NZQA, before they can report credits from assessment against unit standards or deliver courses of study leading to that assessment.

Industry Training Organisations must be granted consent to assess against standards by NZQA before they can register credits from assessment against unit standards.

Providers and Industry Training Organisations, which have been granted consent and which are assessing against unit standards must engage with the moderation system that applies to those standards.

Requirements for consent to assess and an outline of the moderation system that applies to this standard are outlined in the Consent and Moderation Requirements (CMR). The CMR also includes useful information about special requirements for organisations wishing to develop education and training programmes, such as minimum qualifications for tutors and assessors, and special resource requirements.

**Comments on this unit standard**

Please contact [Competenz info@Competenz.org.nz](mailto:Competenz info@Competenz.org.nz) if you wish to suggest changes to the content of this unit standard.